



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE: >90%CA
3. SURFACE QUALITY(S1,S2): 60/40(S/D)
4. WAVEFRONT ERROR(RMS): $\lambda/4@633$ nm(SUBSTRATE)
5. PARALLELISM(S1,S2): <3 arcmin
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:
 FILTERING(S1): $T_{avg}>90\%$, $T_{abs}>85\%@450-775$ nm, 45° AOI
 $R_{avg}>95\%$, $R_{abs}>90\%@823-1200$ nm, 45° AOI
 AR COATING(S2): $R_{abs}<2\%@450-775$ nm, 45° AOI

DRAWING PROJECTION			LBTEK			
	NAME	DATE				
DRAWN	LZHOU	JUL./30th/24	SHORTWAVE DICHOIC MIRROR $\phi 12.7$ mm x 3.2 mm, 805 nm			
APPROVAL	WCHENG	JUL./30th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	0.9 g	2:1	A